



SFW

## P A T E N T

Attorney Docket No.  
033082M172

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of: ) CONFIRMATION NO.: 1732

Takanori MIMURA, et al. )

U.S. Serial No.: 10/647,433 ) Group Art Unit: 1765

Filed: August 26, 2003 ) Examiner: Binh X. Tran

For: SILICON ETCHING METHOD

## RESPONSE TO ELECTION REQUIREMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir :

A response to the Office Action mailed August 29, 2005 is due by September 29, 2005.

The Action required election between the following:

Species A, with a SiO<sub>2</sub> film mask, and a RF power flux density at 6.8 to 12.5 W/cm<sup>2</sup>; and

Species B, with a resist film, and a RF power flux density at 2.55 to 5.67 W/cm<sup>2</sup>.

Applicants hereby elect Species A for examination in this application. Applicants advise that the elected species corresponds to all of claims 1-15 and 17-19. Applicants also advise that no change in the inventorship of the application would be required by cancellation of non-elected claim 16.

Applicants reserve the right to file divisional application(s) for any non-elected claims in due course.

It is submitted that this application now is in condition for examination on the merits and early action in that regard is solicited.

Respectfully submitted,  
SMITH, GAMBRELL & RUSSELL, LLP



Michael A. Makuch – Registration No. 32,263  
1850 M Street, NW – Suite 800  
Washington, DC 20036  
Tel : 202 263 4300  
Fax : 202 263 4329

Date : September 26, 2005